## UNITED STATES PATENT AND TRADEMARK OFFICE

Inventor: TUUNG LUOH	)
Serial No: 10/715,558	) Attorney Docket No.: MIC910137
Filed: November 19, 2003	)
Title: METHOD OF FORMING A POLYSILICON LAYER COMPRISING	) )
MICROCRYSTALLINE GRAINS	)

## SUBMISSION OF REVOCATION OF POWER OF ATTORNEY AND GRANT OF POWER OF ATTORNEY

Assistant Commissioner of Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Applicants hereby submit the attached Revocation of Power of Attorney and Grant of Power of Attorney in the above-identified application. Should there be any questions with respect to this submission a representative of the Patent Office is requested to contact the undersigned.

Respectfully submitted,

Registration No. 44,615

**TUUNG LUOH** 

Date: January 18, 2005

By:

Poh C. Chua

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PCC/mce

Customer No. 28970



PATENT Customer No. 28970

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Patent Application and Patent Numbers:

See attached "Schedule A"

## REVOCATION OF POWER OF ATTORNEY AND GRANT OF NEW POWER OF ATTORNEY

The undersigned, a representative authorized to sign on behalf of the assignee owning all of the interest in the listed and pending patent applications and issued patents on the attached sheet (Schedule A), hereby revokes all previous powers of attorney or authorization of agent granted in these patents before the date of execution hereof and appoints all the attorneys associated with Customer Number 28970.

Correspondence in this matter should be directed to:

Yitai Hu SHAW PITTMAN LLP 1650 Tysons Boulevard McLean, Virginia 22102 Telephone: (703) 770-7900 Fax (703) 770-7901

Date: January 10, 2005

MACRONIX INTERNATIONAL CO., LTD.

· /

Name: \_\_

Title: Director

P & Legal Office

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SERIAL NUMBER FILING DATE STITLE PATENT NUMBER ISSUE DATE							
SERIAL NUMBER	FILING DATE	TO THE STATE OF TH	PATENT NUMBER	ISSUE DATE			
		Ono Interpoly Dielectric Flor Flash					
		Memory Cells and Method for					
		Fabricating The Same Using a	·				
		Single Wafer Low Temperature					
10/237,668	9/10/2002	Deposition Process	6,777,764	8/17/2004			
10/201,000	0.10.202	Method for Removing Fences	-1, ,				
		Without Reduction of Ono Film					
10/230,328	8/29/2002	Thickness	6,677,255	1/13/2004			
10/230,320	0/25/2002	Programming A Flash Memory	0,077,200	1710/2004			
10/220 666	8/29/2002	Cell	6,760,257	7/6/2004			
10/230,666	0/29/2002	Cell	0,700,237	11012004			
		Apparatus and Mathaditas					
10/100 000	514/0000	Apparatus and Method for	0.707.000	0/7/0004			
10/426,833	5/1/2003	Inhibiting Dummy Cell Over Erase	6,787,860	9/7/2004			
		Protection Layer to Prevent Under-					
10/076,629	2/19/2002	Layer Damage During Deposition	6,573,177	6/3/2003			
		Sensing Method for EEPROM					
10/151,150	5/21/2002	Refresh Scheme	6,639,839	10/28/2003			
		Semiconductor Device with					
		Minimal Short-Channel Effects and					
10/101,930	3/21/2002	Low Bit-Line Resistance	6,555,844	4/29/2003			
		Sonos Component Having High					
10/101,922	3/21/2002	Dielectric Property	6,498,377	12/24/2002			
		Method for Forming An Oxide					
10/101,931	3/21/2002	Layer on a Nitride Layer	6,551,879	4/22/2003			
10.101,001	0.2	Structure for Preventing Salicide	0,00.,0.0				
10/186,619	7/2/2002	Bridging and Method Thereof	6,677,199	1/13/2004			
10/100,010		Method of Preventing Tungsten	0,011,100				
10/132,286	4/26/2002	Plugs From Corrosion	6,703,301	3/9/2004			
10/102,200	4/20/2002	Method for Forming A Phase	0,700,001	0/0/2004			
10/197,896	7/19/2002	Change Memory	6,759,267	7/6/2004			
10/19/,090	111912002	Memory Device and Operation	0,739,207	11012004			
10/014 770	0/0/2002	Thereof	6 700 600	9/7/2004			
10/214,770	8/9/2002	Method for Forming A Phase	6,788,602	9///2004			
40/047 077	5470004		A1/A				
10/847,277	5/17/2004		N/A	NA			
101170 005	0.004.0000	Neural Network for Determining					
10/176,065	6/21/2002	the Endpoint in a Process	N/A	NA			
		Photoresist Pump Dispense					
10/387,489	3/14/2003		N/A	NA			
		Cleaning Systems With Monitaring					
10/439,014	5/16/2003	Functions	N/A	NA			
10/600,700	6/23/2003	Peer Version Control System	N/A	NA			
10/667,447	9/23/2003	Batch Order Change System	N/A	NA			
		Elimination of the Fast-Erase					
10/733,230	12/12/2003	Pheonomena in Flash Memory	N/A	NA .			
		Cleaning Method Using Ozone DI					
10/731,150	12/10/2003		N/A	NA			
,		Endpoint Detection in					
		Manufacturing Semi-Conductor		a.			
10/685,484	10/16/2003	_	N/A	NA			
10/000,707	10/10/2000	1501100	11//	13/3			

SERIAL NUMBER	FILING DATE	TITLE	PATENT NUMBER	ISSUE DATE	
		Program/Erase Method for P-			
		Channel Charge Trapping Memory			
10/857,866	6/2/2004	Device	N/A	NA	
		·			
	ļ	Method for Reducing Dimensions		•	
10/465,852	6/20/2003	Between Patterns on a Hardmask	N/A	NA	
	1	Method for Reducing Dimensions			
10/739,049	12/19/2003	Between Patterns on a Photoresist	N/A	NA	
		Structure for Preventing Salicide			
10/673,359	9/30/2003	Bridging and Method Thereof	N/A	NA	
		Non-Volatile Memory Cell and			
10/873,142	1/14/2004	Operating Method	N/A	NA	
		Memory Device With Built-In Error-			
10/237,082	6/2/2003	Correction Capabilities	N/A	NA	
		Memory Device With Built-In Error-			
10/449,590	6/2/2003	Correction Capabilities	N/A	NA	
		Semi-Conductor Device With			
	_	Minimal Short-Channel Effects and			
10/361,681	2/11/2003	Low Bit-Line Resistance	N/A	NA	
		Method of Forming a Polysilicon			
		Layer Compressing			
10/715,558	11/19/2003	Microcrystalline Grains	N/A	NA	
10/414,048	4/16/2003	ONO Dielectric for Memory Cells	N/A	NA	
	•				
		Method of Integrating The			
		Fabrication Process for Integrated		l	
10/418,121	4/18/2003	Circuits and Mem Devices	N/A	NA	
		Method for Controlling a Butterfly		l	
10/387,487	3/14/2003	Valve	N/A	NA	
10/653,892	9/4/2003	A Non-Volatile Flash Memory	N/A	NA	
	i	Fabrication Method of Sub-			
		Resolution Pitch for Integrated	A1/ A		
10/703,453	11/10/2003	Circuits	N/A	NA	
		Make ad for Dadusting Dimensions			
	40/40/0004	Method for Reducting Dimensions Between Patterns on a Photoresist	A1/A	NA.	
09/978,546	10/18/2001		IN/A	NA	
404477.445	0/04/0000	Method for Eliminating Standing	NI/A	NA	
10/177,145	6/24/2002	Waves in a Photoresist Profile	N/A	INA	
		Method for Detecting Solvent			
40/044 400	0/42/2002	Leakage During Manufacture of a Semi-Conductor Device	NI/A	NA	
10/241,486	9/12/2002	Memory Device and Method of	N/A	INA	
40/000 007	0/00/0000		NI/A	NA	
10/223,327	8/20/2002	Manufacturing The Same Method of Fabricating ONO	N/A	14/	
	•	Dielectric for Non-Volatile			
40/276 225	2/2/2002		N/A	NA	
10/376,225	3/3/2003	Memories  Method of Forming An Embedded	13/7	11/	
40/007 400	2/4 4/2002	_	N/A	NA	
10/387,488	3/14/2003	ROM	IN/A	INA	
40/694 000	10/0/2002	Defect Reduction Using Pad	NI/A	NA	
10/681,099	10/9/2003	Conditioner Cleaning	N/A	IAV.	

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SERIAL NUMBER	FILING DATE	AND SEA TITLE SERVICE	PATENT NUMBER	ISSUE DATE
		Method of Preventing Over-Erase		
		of Memory Devices		
		Method for Eliminating Standing		
10/176,061	6/21/2002	Waves in a Photoresist Profile	N/A	NA
		Self-Aligned Patterning in Dual		
10/076,630	2/19/2002	Damascene Process	N/A	NA
<u> </u>		Method for Forming Tungsten		
		Plugs to Prevent Corrosion		
10/137,406	5/3/2002	Complexity	N/A	NA
10.101,100		Method for Forming Self-Aligned		
10/186,892	7/2/2002	Salicides	N/A	NA
707.000,002		Method for Reduced Photoresist		
10/210,032	8/2/2002	Usage	N/A	NA
10.2.10,002	0,2,2002	Method of Forming Self-Aligned		
10/403,060	4/1/2003	Contracts	N/A	NA
10/40/0,000	17 11 2 0 0 0	Method for Suppressing Boron		
		Penetration by Implantation in P*		
10/656,224	9/8/2003	Mosfets	N/A	NA
10/000,22-1	0,0,2000	Non-Volatile Memory Cell and		
10/756,777	1/14/2004	Operating Method	N/A	NA NA
10/730,777	171472004	Sub-90nm Space and Hole	14// \	
		Patterning Using 248nm		
		Lithography with Plasma-		
60/390,183	6/21/2002	Polymerization Coating	N/A	NA
50/550, 105	0/2 1/2002	Method for Eliminating Polycide		
		Voids Through Nitrogen		
		Implantation	N/A	NA
		Implantation	19//	
		Method for Reducing Dimensions		
10/465,848	6/20/2003	Between Patterns on a Photomask	ΝΙ/Δ	NA
10/405,646	0/20/2003	Method of Modulating Threshold	IN/A	INA .
10/417,105	4/17/2003		N/A	NA
10/417,100		Method for Forming Shallow	IN/A	INA
		Trench Isolation With Control of		
10/205 402	2/42/2002		NI/A	NIA.
10/385,483	3/12/2003		N/A	NA
10/276 220	1	Method for Plymer Removal After	NI/A	المام
10/376,229			N/A	NA
404405-050		Method for Shrinking Dimensions	<b>51/4</b>	1
0/465,850			N/A	NA
	1	Method and System for	•	
0.01.5		Lithography Using Phase-Change		
10/315,003	12/10/2002	Material	N/A	NA

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